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(12) **United States Design Patent**
Kuwabara et al.

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(54) **ELECTRODE PLATE FOR A PLASMA
PROCESSING APPARATUS**

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(**) Term: **14 Years**

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(30) **Foreign Application Priority Data**

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(51) **LOC (10) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/182**

(58) **Field of Classification Search**
USPC D13/182; D15/144, 144.1, 199;
118/715; 414/935-941, 147, 217;
156/345.53; 279/128; 361/230, 233,
361/234; 204/193, 194, 279, 280, 281, 282,
204/283, 284, 285, 286.1, 297.01; 205/118,
205/123; 200/293, 302.1, 308

See application file for complete search history.

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(57) **CLAIM**

The ornamental design for an electrode plate for a plasma
processing apparatus, as shown and described.

DESCRIPTION

FIG. 1 is a front view of an electrode plate for a plasma
processing apparatus showing our new design, the rear view
being identical;

FIG. 2 is a right side view thereof, the left side view being
identical;

FIG. 3 is a top plan view thereof;

FIG. 4 is a bottom plan view thereof;

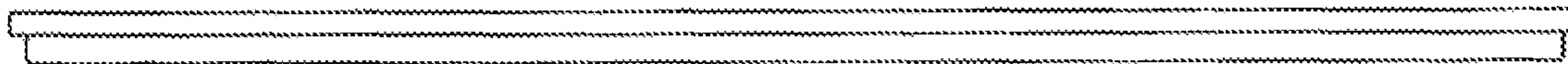
FIG. 5 is an enlarged view of a portion of the electrode plate
for a plasma processing apparatus of FIG. 1 taken along line
1-1 and line 2-2 of FIG. 3;

FIG. 6 is an enlarged cross sectional view thereof, taken along
line 3-3 of FIG. 5; and,

FIG. 7 is a perspective view of the electrode plate for a plasma
processing apparatus of FIG. 1.

The features shown only in broken lines depict environmental
subject matter only and form no part of the claimed design.

1 Claim, 7 Drawing Sheets



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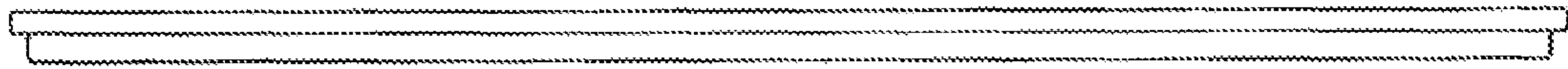


Figure 1

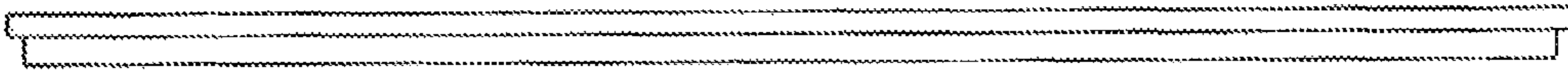


Figure 2

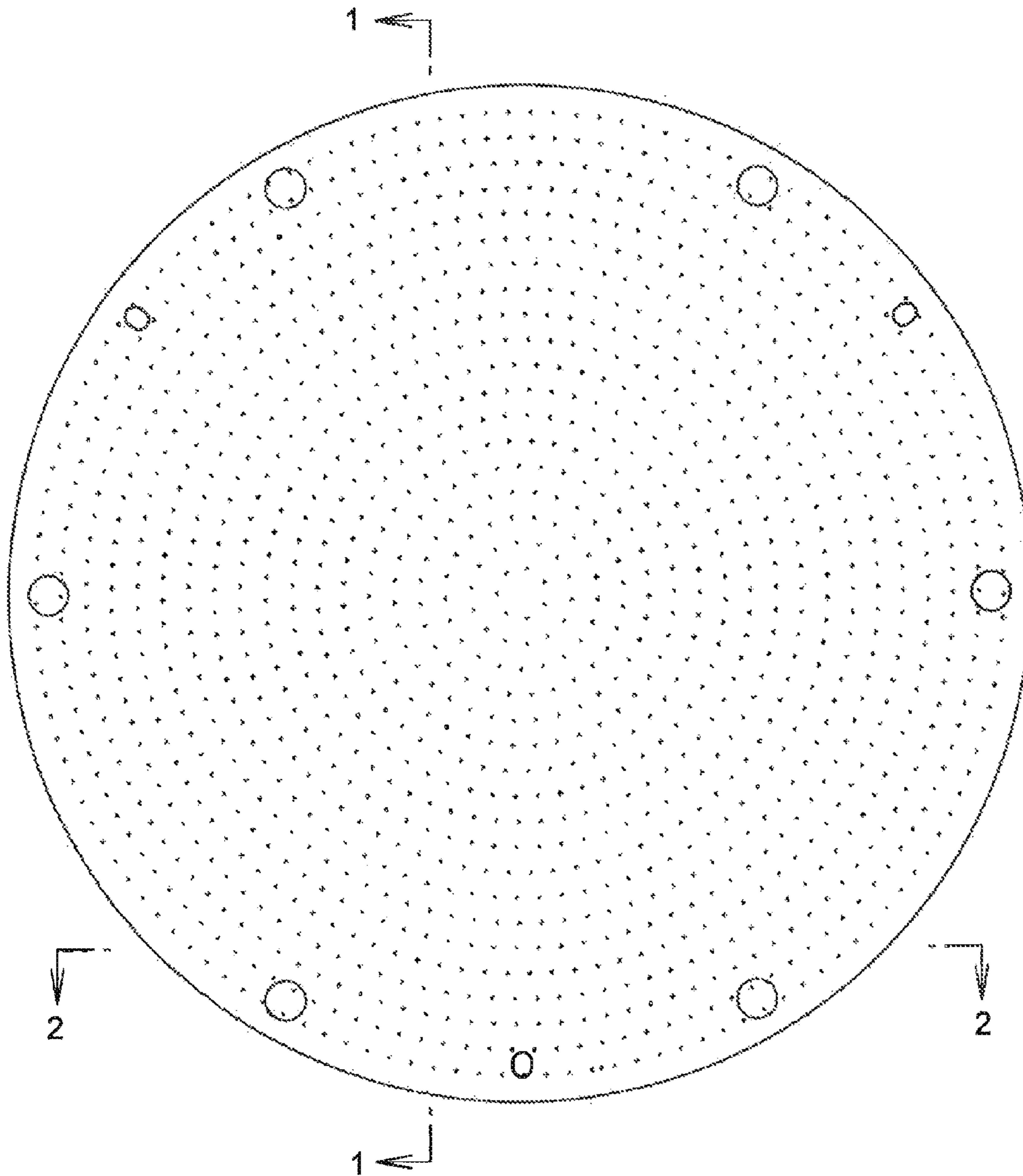


Figure 3

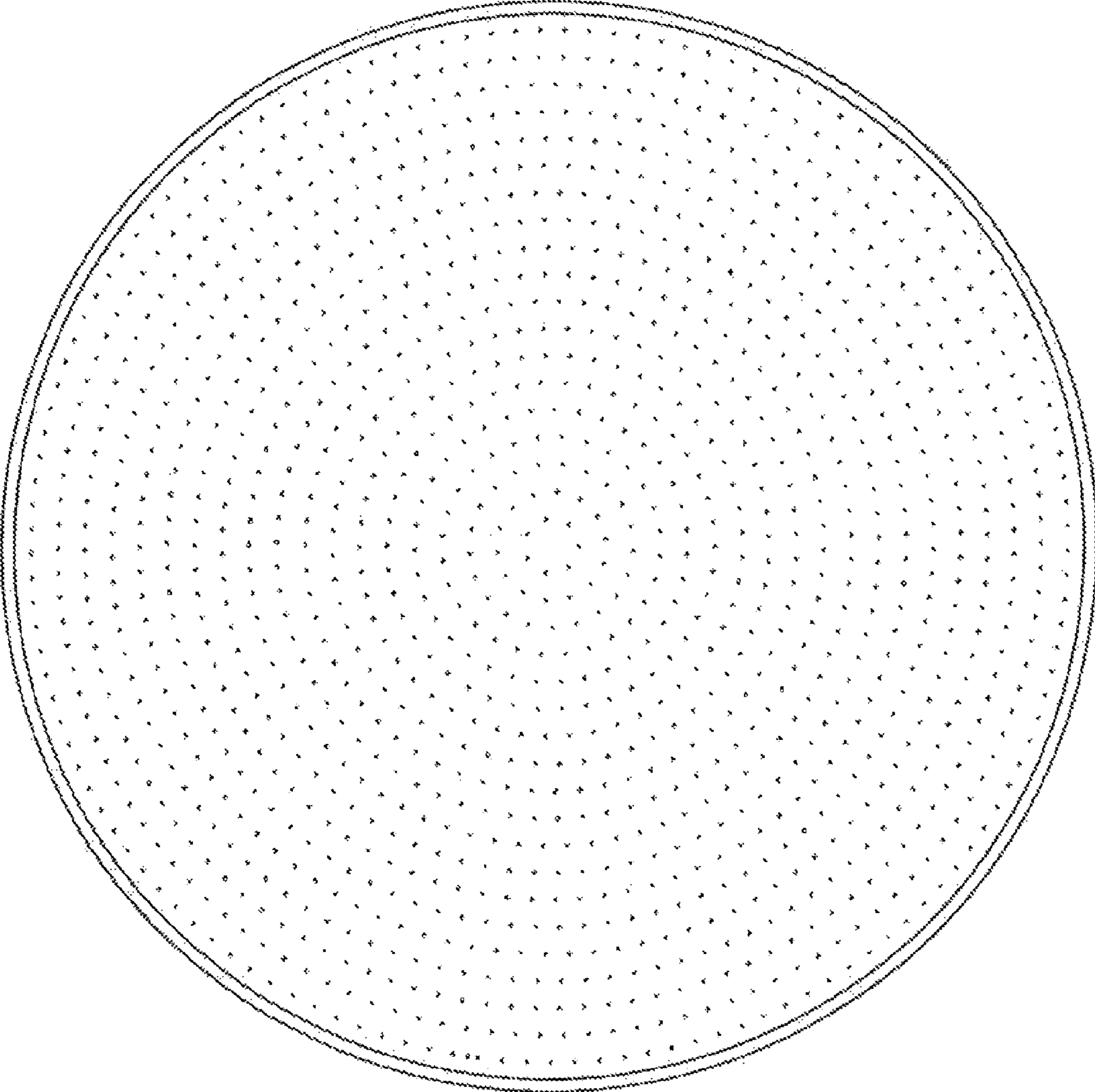


Figure 4

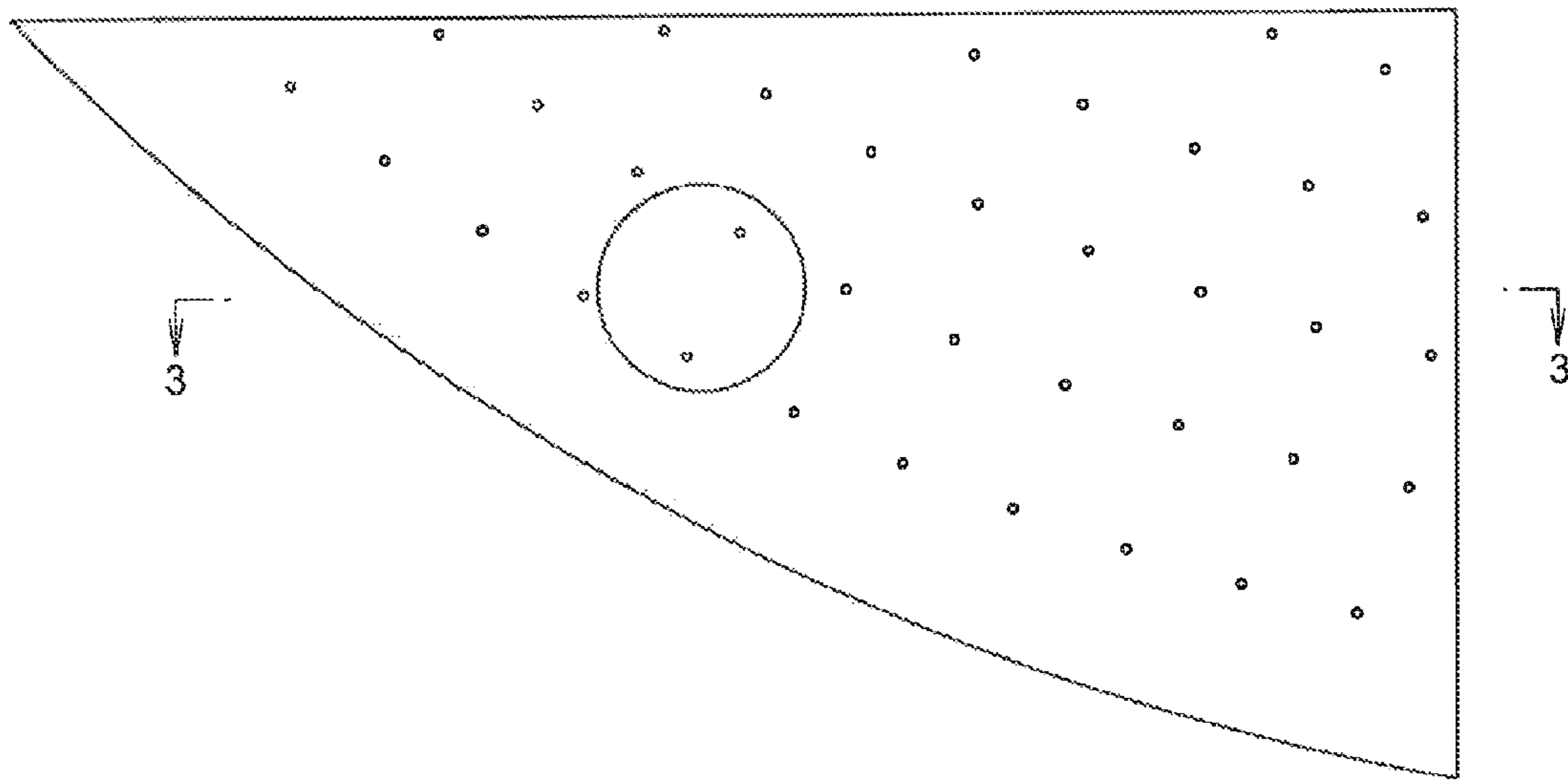


Figure 5

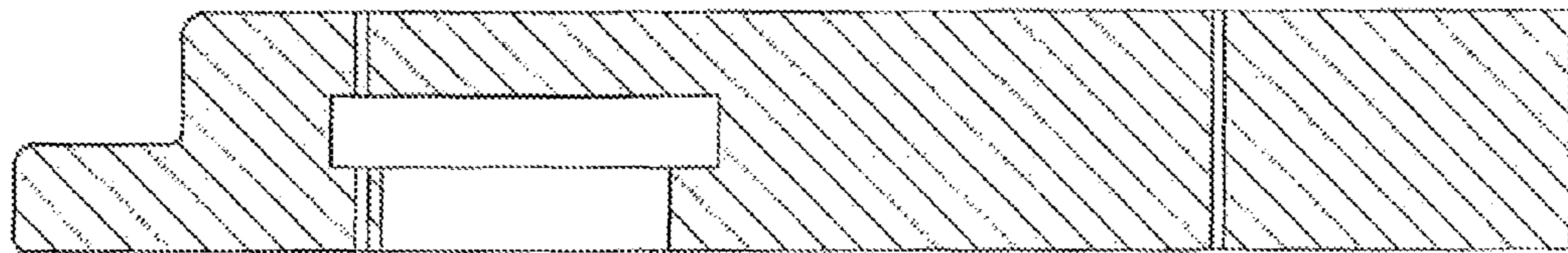


Figure 6

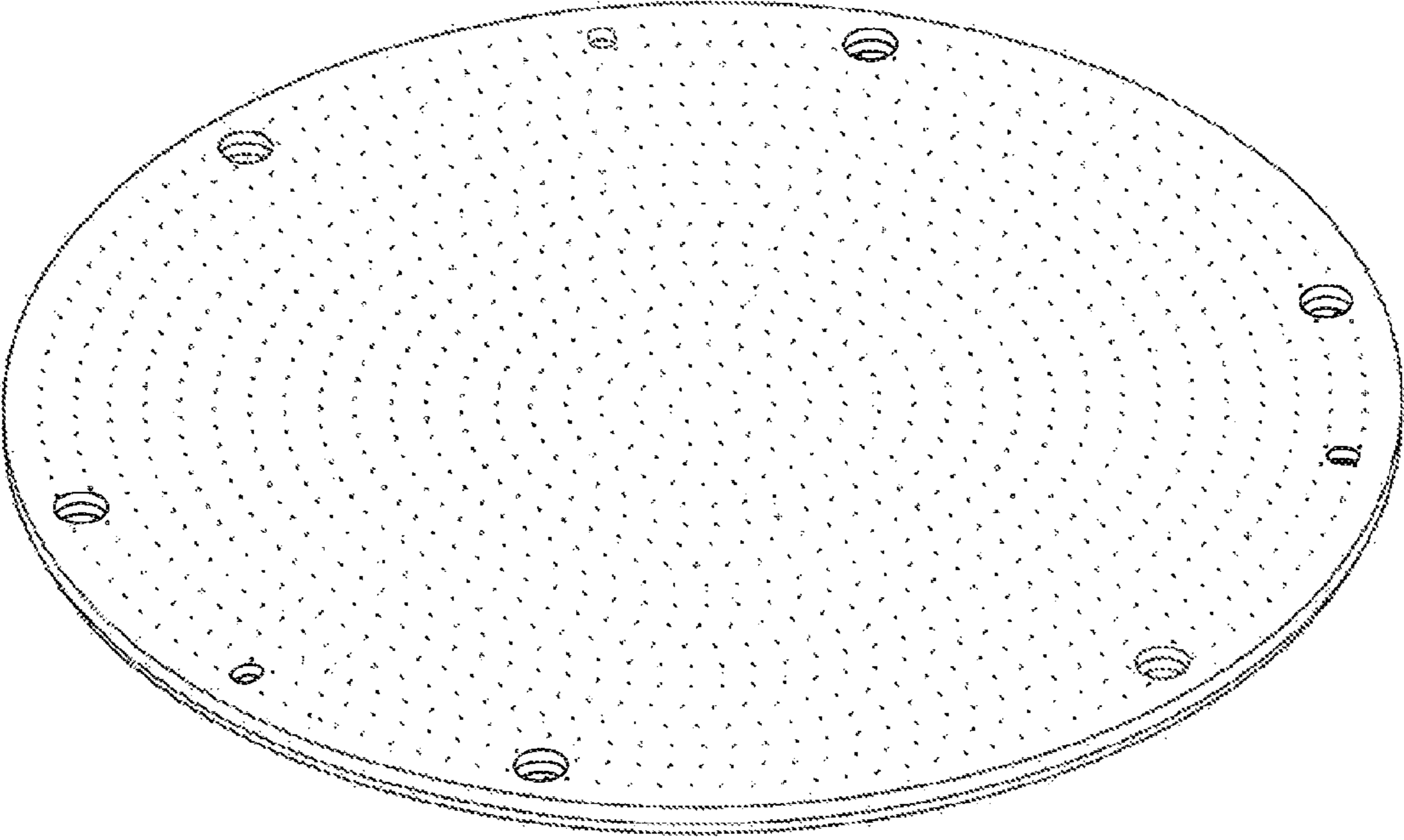


Figure 7